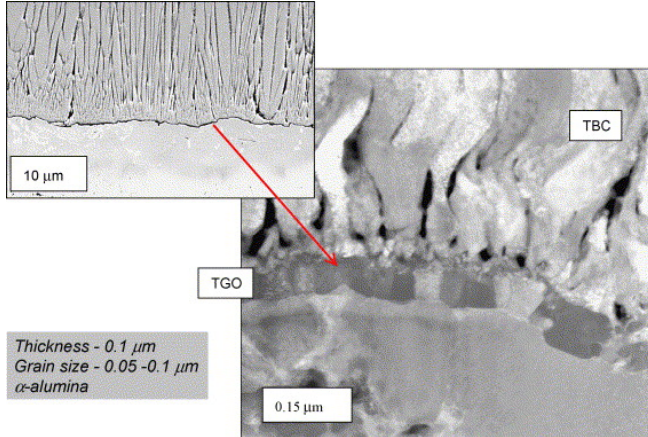


# Interfacial Phases & Transport Kinetics

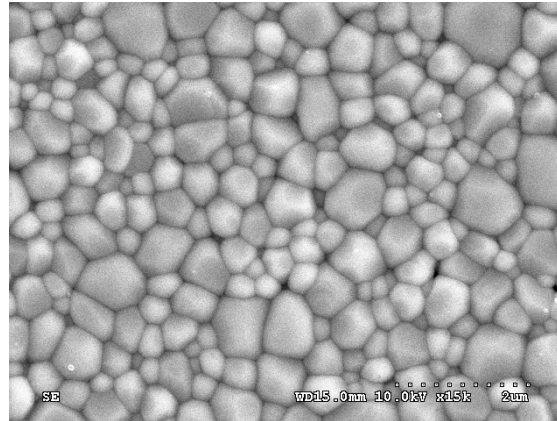
Shen J. Dillon

# Interfacial Kinetic Engineering

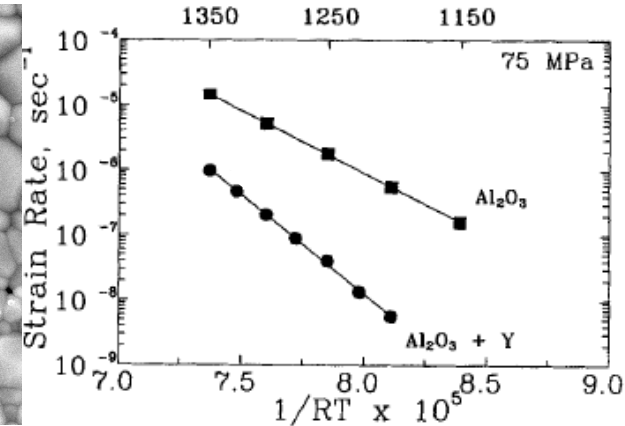
## Slow Boundaries



I. Spitsberg, K. More, *Mat. sci., & Eng. A* 2006

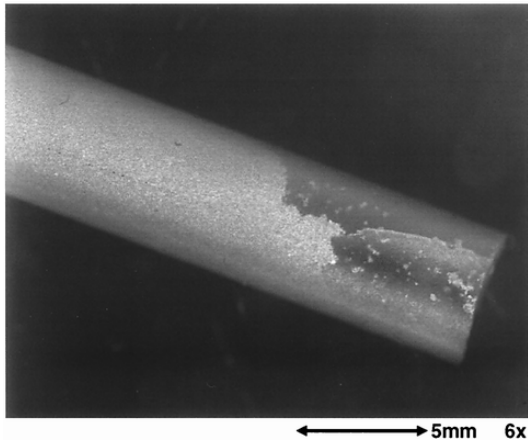


S. Ma

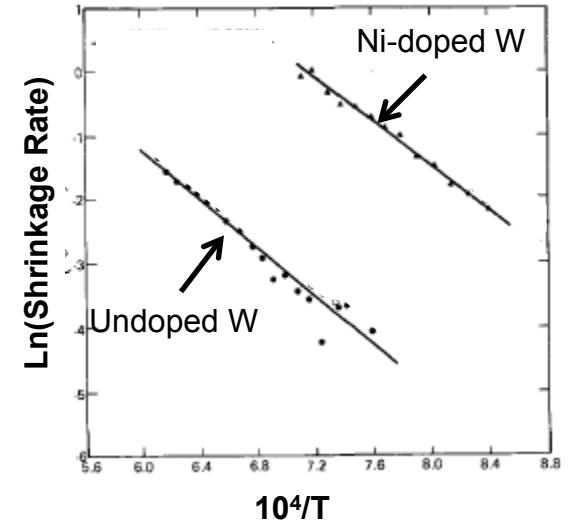
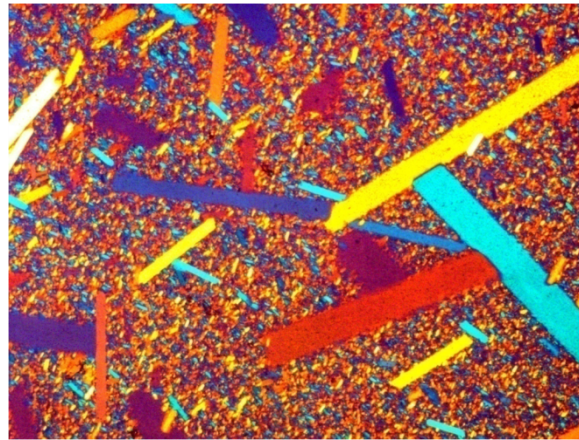


J.D. French, et al. *JACerS* (1994)

## Fast Boundaries

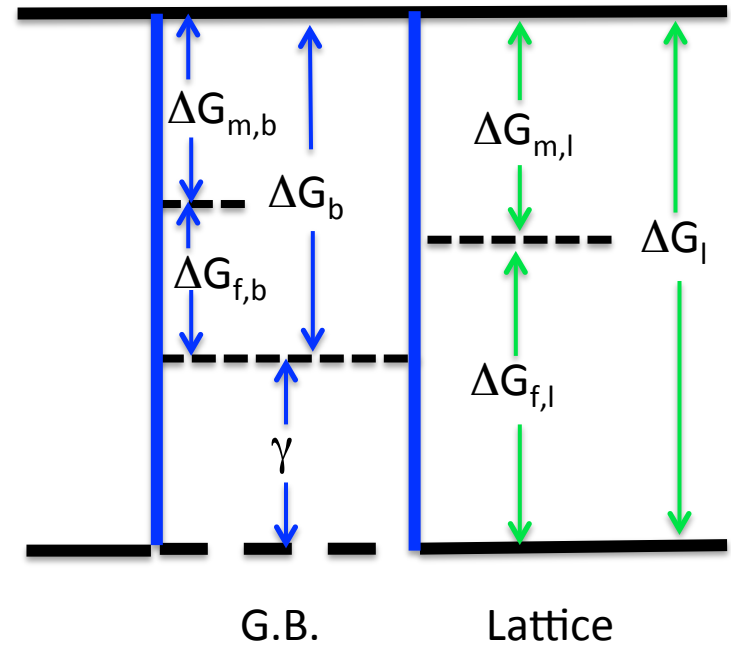
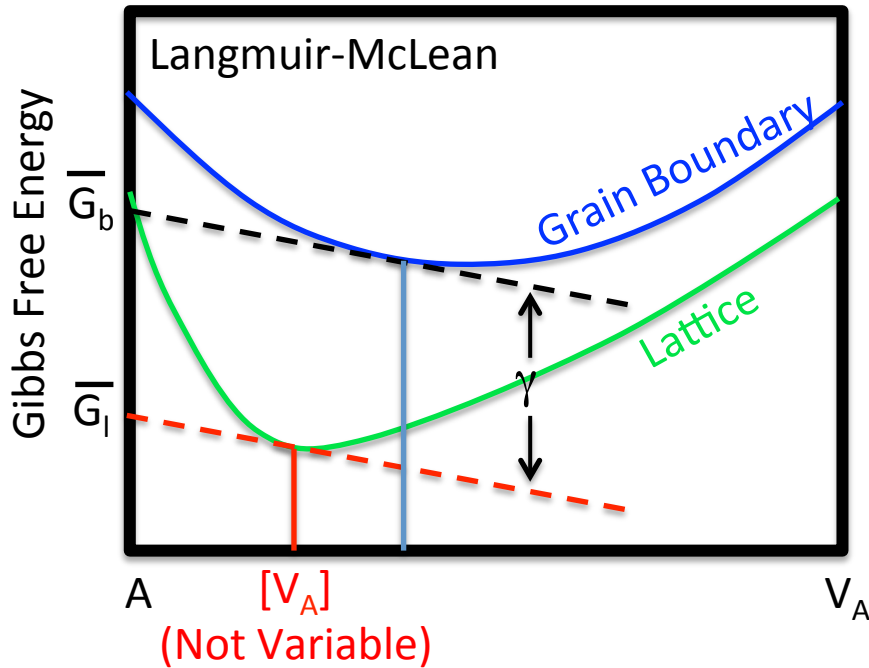


Curtis Scott, et al., *JACerS*, 2002



German, Munir, *Met. Trans. A*, (1974)

# Linking Thermodynamics & Kinetics

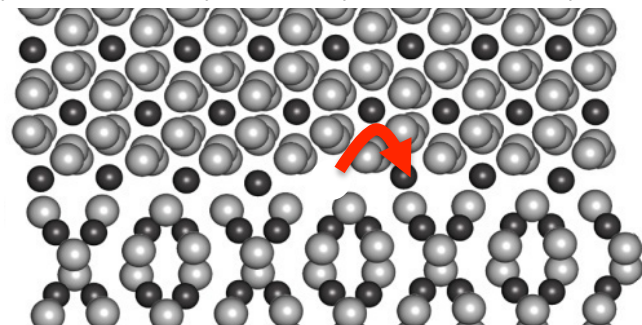
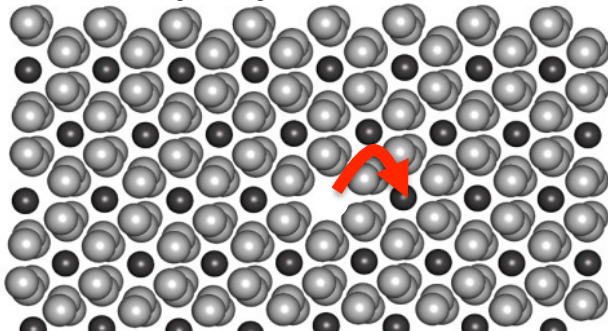


$$D = ga^2 C_v \Gamma$$

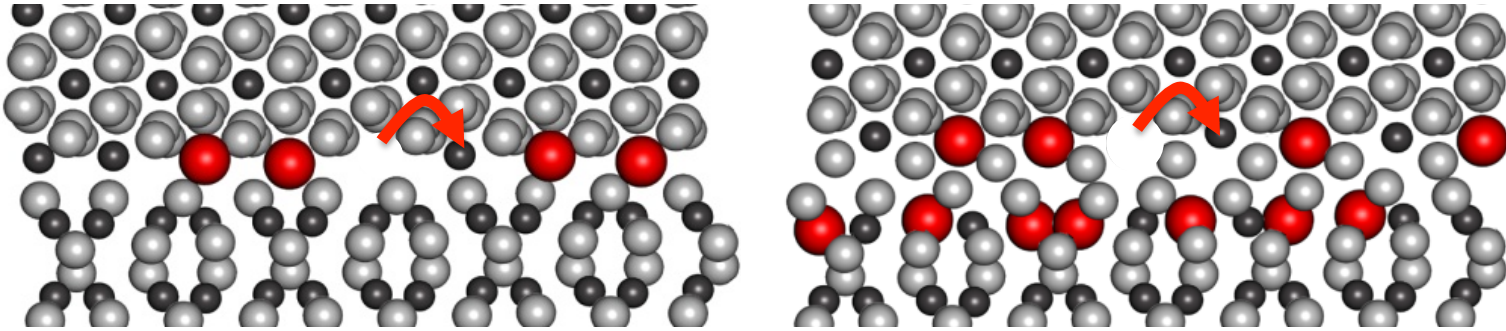
$$C_v = \exp(\Delta S_f/k) \exp(-\Delta H_f/kT)$$

$$\Gamma = v^* \exp(-\Delta H_m/kT)$$

$$\gamma = \rho [RT \ln(ga_b^2 v_b^* / g\kappa_l a_l^2 v_l^*) - T(\Delta S_{f,l} - \Delta S_{f,b}) + (\Delta H_{f,l} - \Delta H_{f,b}) + (\Delta H_{m,l} - \Delta H_{m,b})]$$



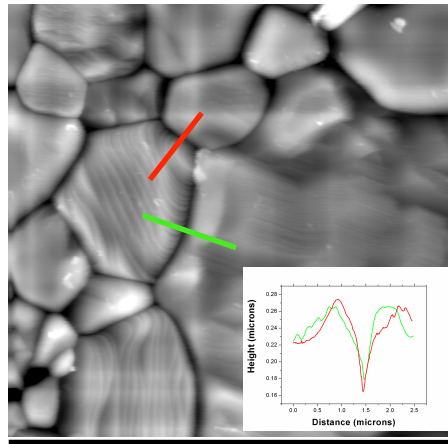
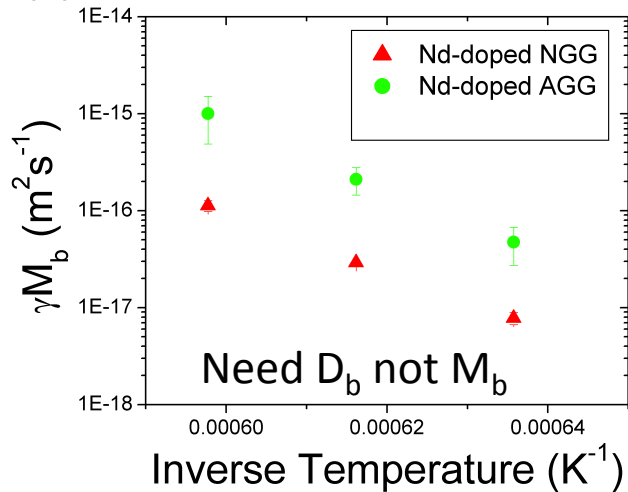
# Comparing Complexions ( $\Delta H$ & $\Delta S$ )



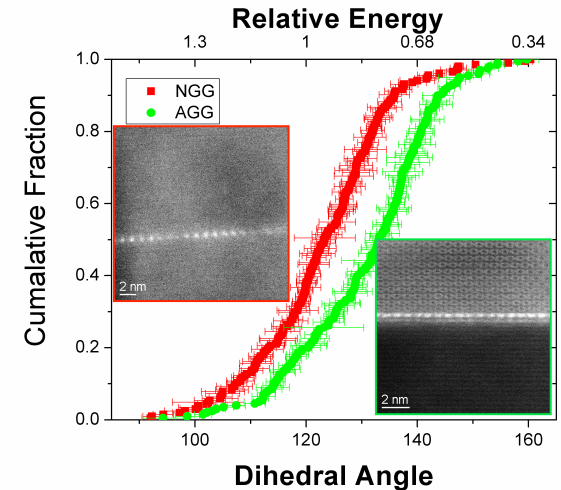
$$\Delta\gamma = \Delta\rho [RT \ln(ga_{\perp}^2 v_{\perp}^* / g\kappa_{\parallel} a_{\parallel}^2 v_{\parallel}^*) - T(\Delta S_{f,\perp} - \Delta S_{f,\parallel}) + (\Delta H_{f,\perp} - \Delta H_{f,\parallel}) + (\Delta H_{m,\perp} - \Delta H_{m,\parallel})]$$

Simplifying Assumptions:  $\Delta\gamma = \Delta\rho [-T(\Delta S_{\perp} - \Delta S_{\parallel}) + (\Delta H_{\perp} - \Delta H_{\parallel})]$

Approach:

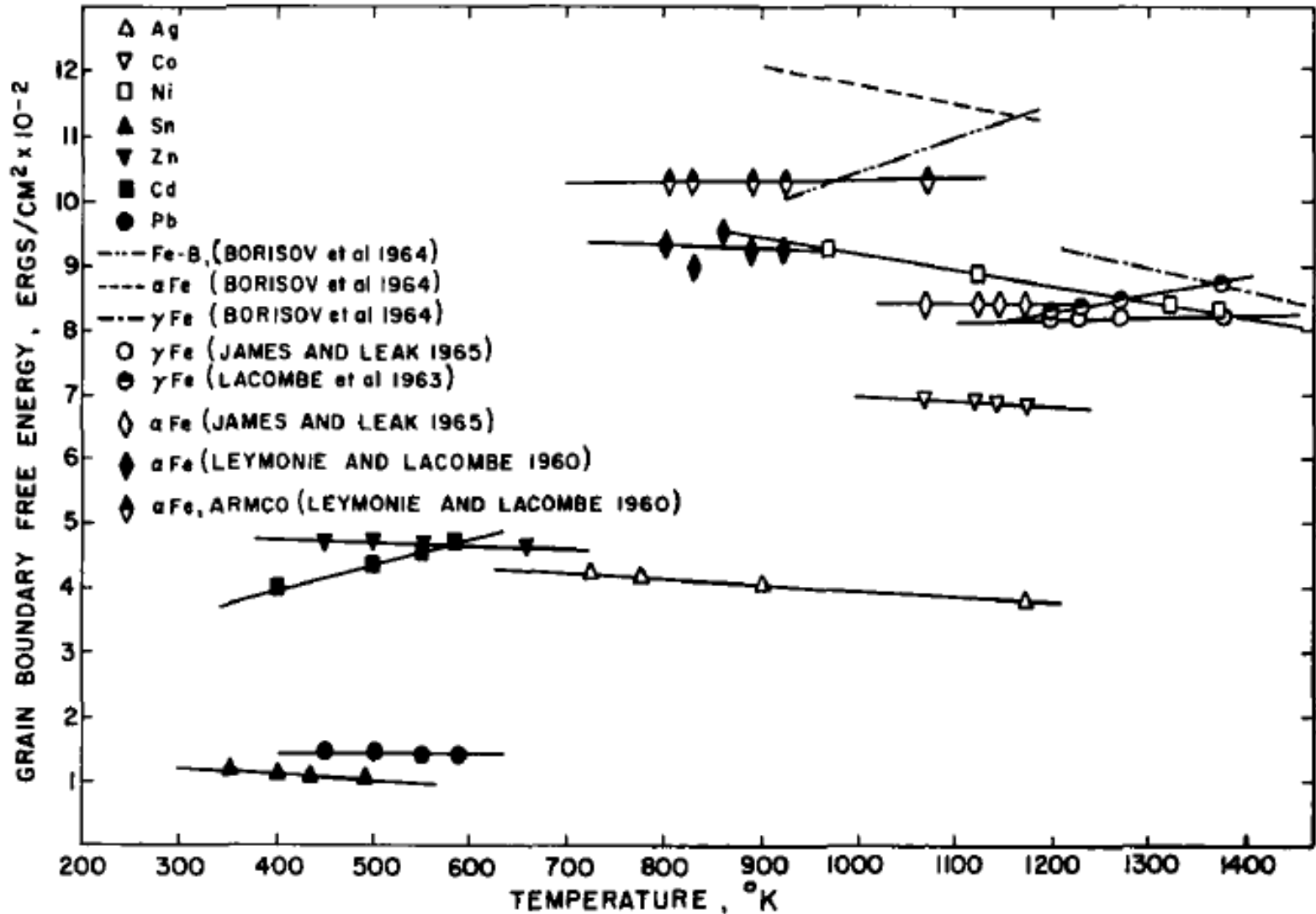


10 micron

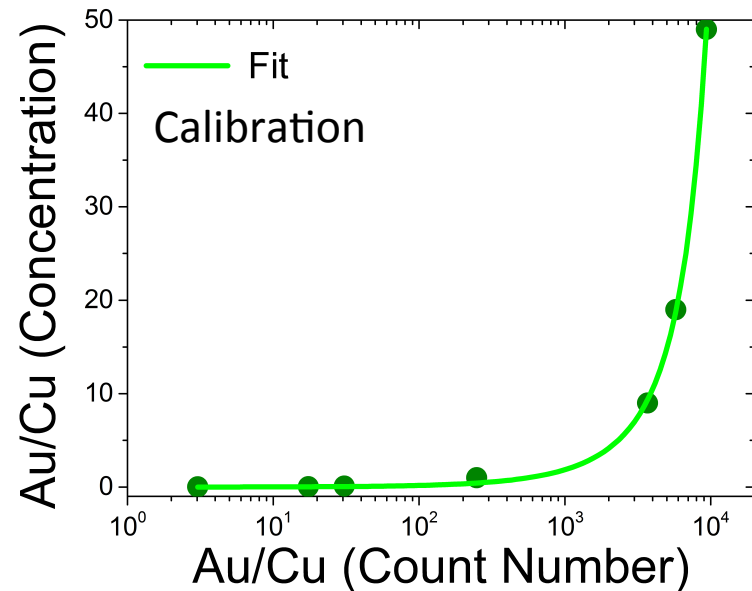
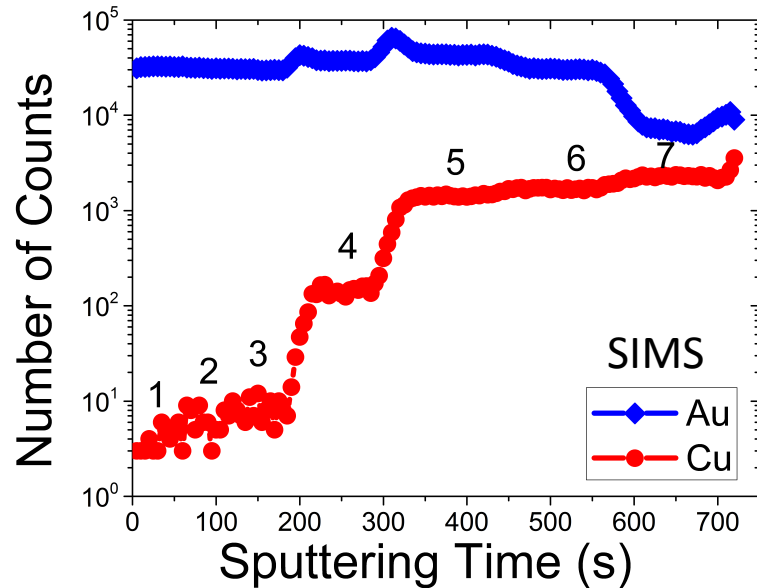
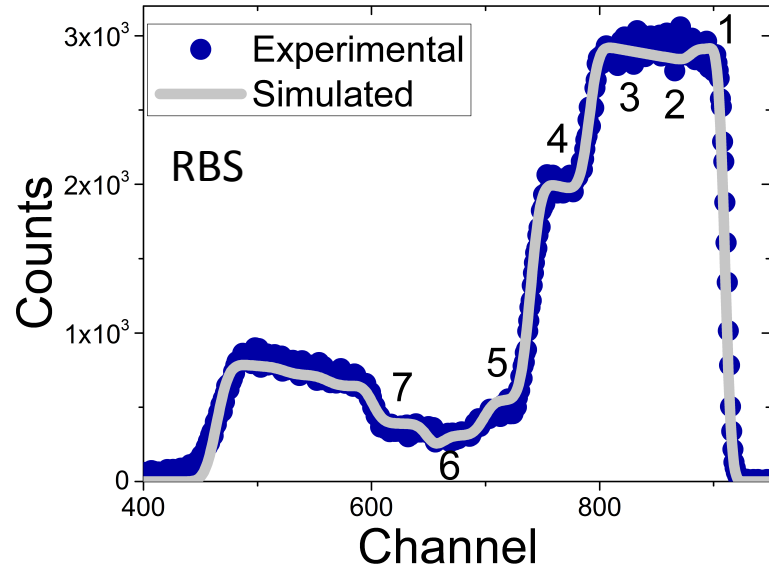
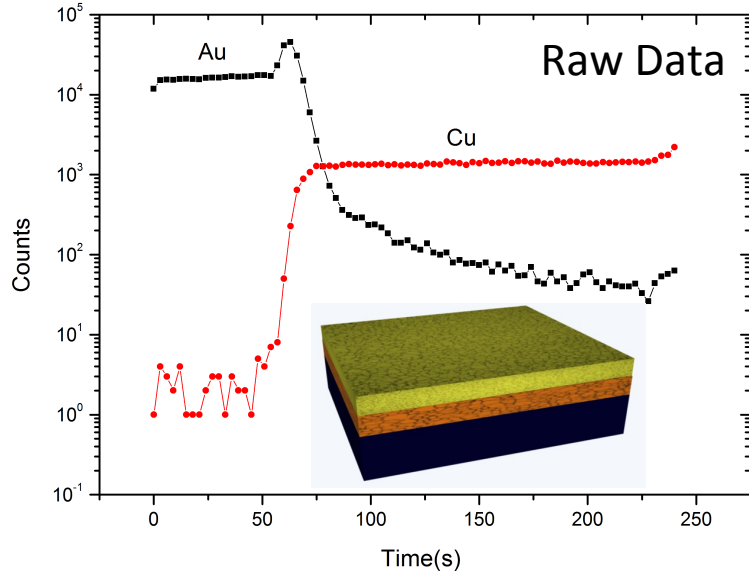


Check:  $\gamma = \rho [RT \ln(ga_b^2 v_b^* / g\kappa_a a_l^2 v_l^*) - T(\Delta S_{\perp} - \Delta S_b) + (\Delta H_{\perp} - \Delta H_b) + (P\Delta V_{\perp} - P\Delta V_b)]$

# Early Tests of Borisov Model

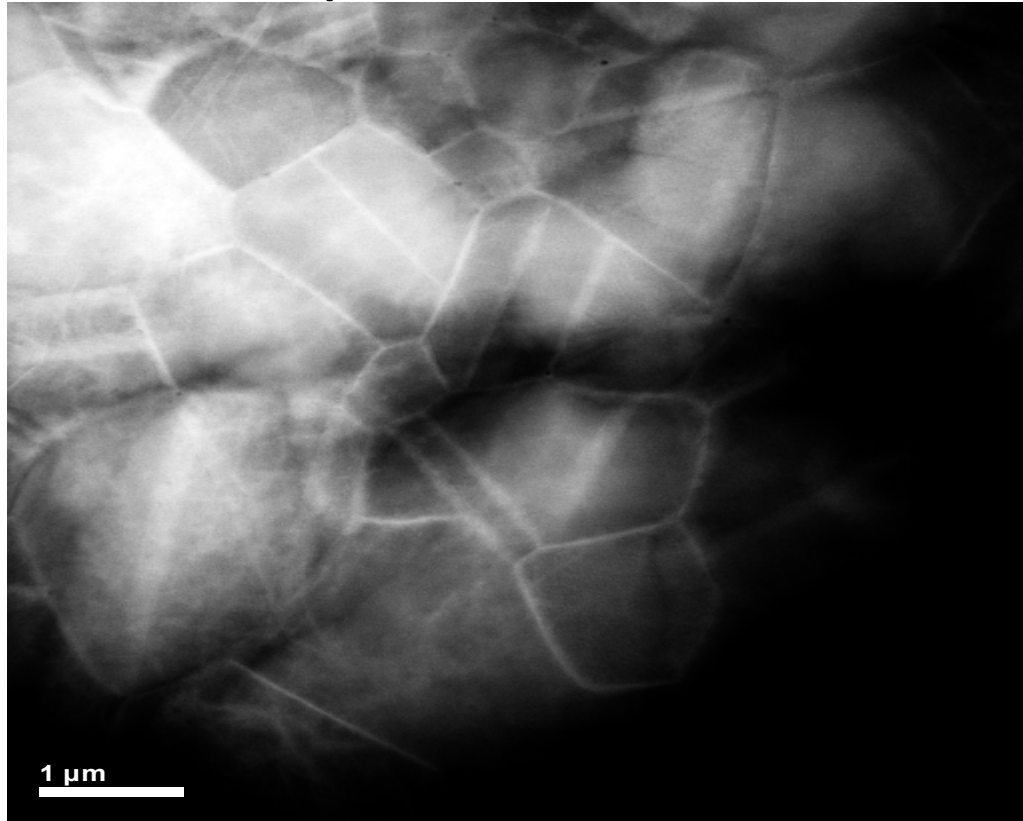


# Sample Preparation and Testing

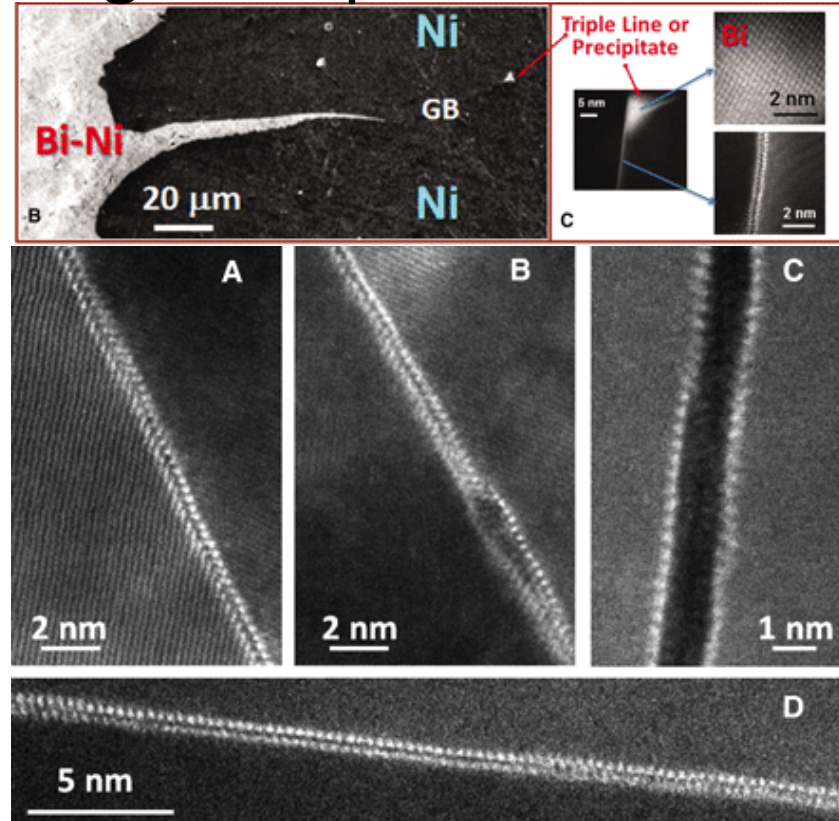


# Bi-doped Ni

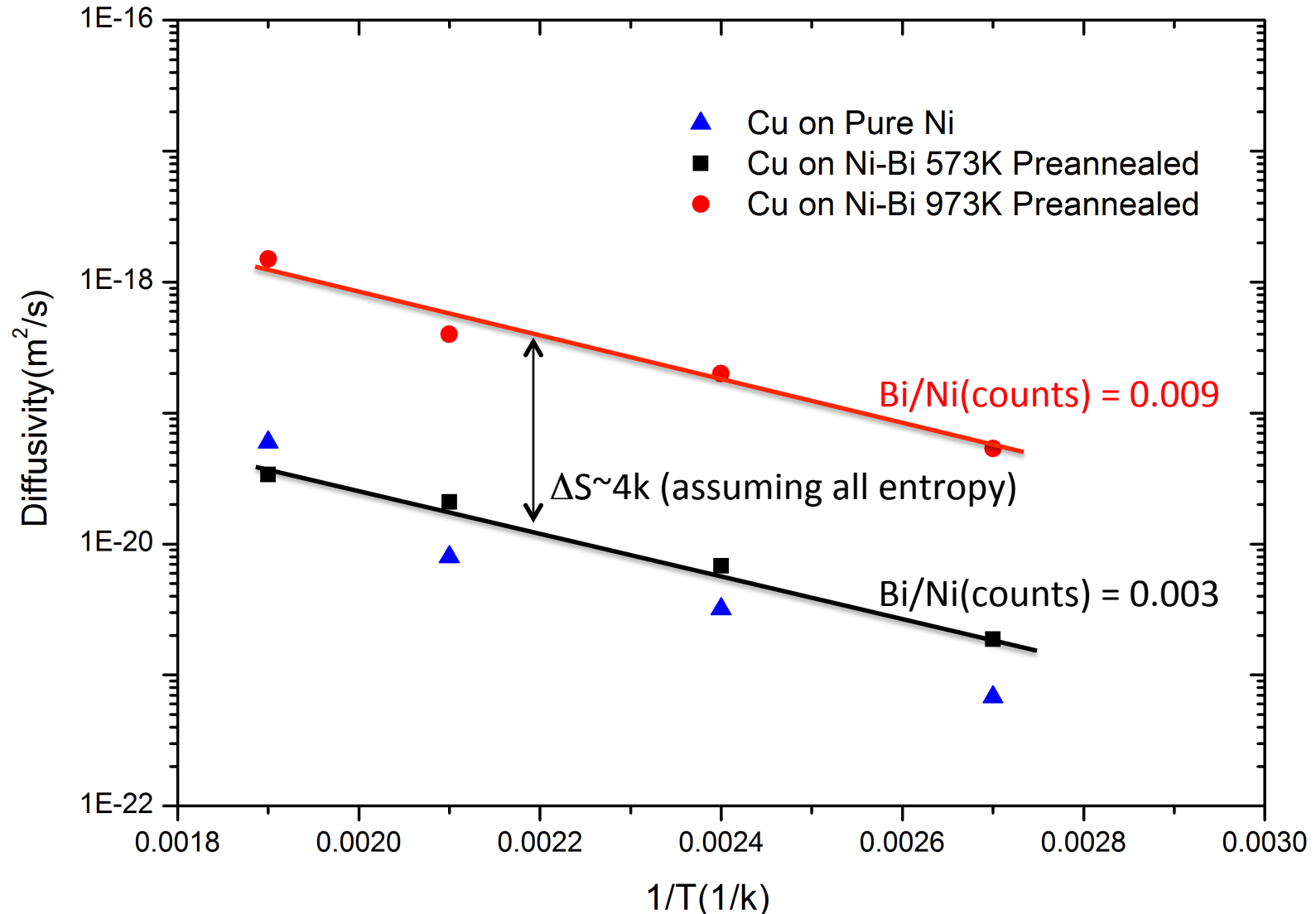
Low Temperature 300°C



High Temperature 700°C



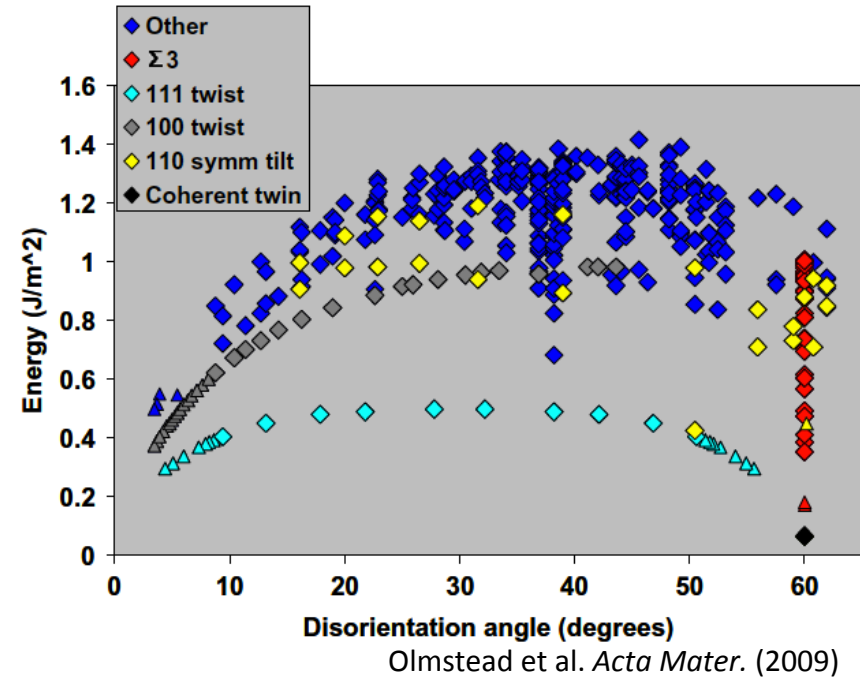
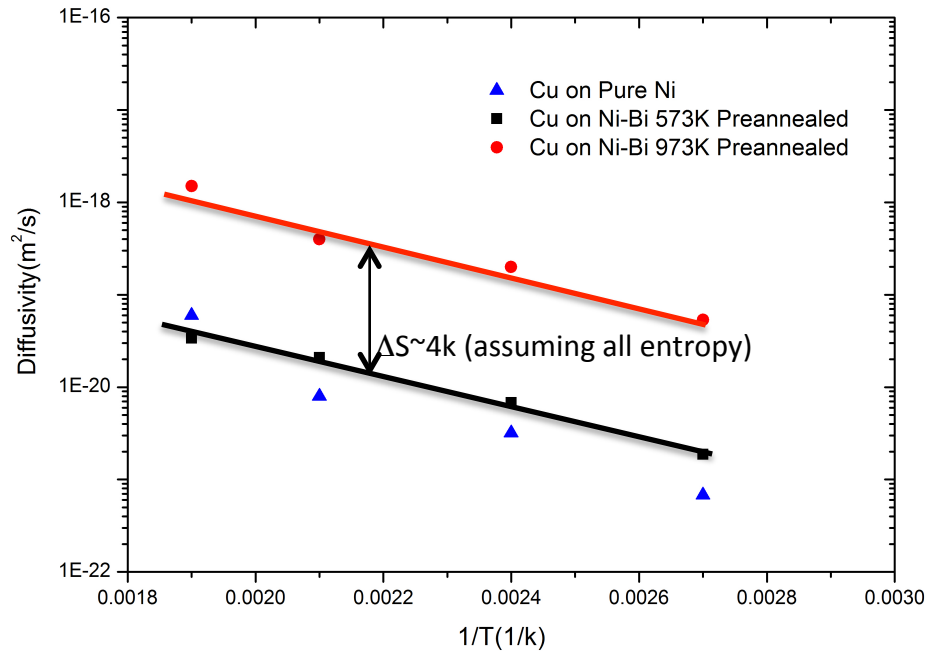
# Cu diffusion into Bi doped Ni Matrix



Cu diffusion into Ni and Ni-Bi (GB doped) samples



# Cu diffusion into Bi doped Ni Matrix



$\Delta S \sim 4k$  (assuming entropy only)

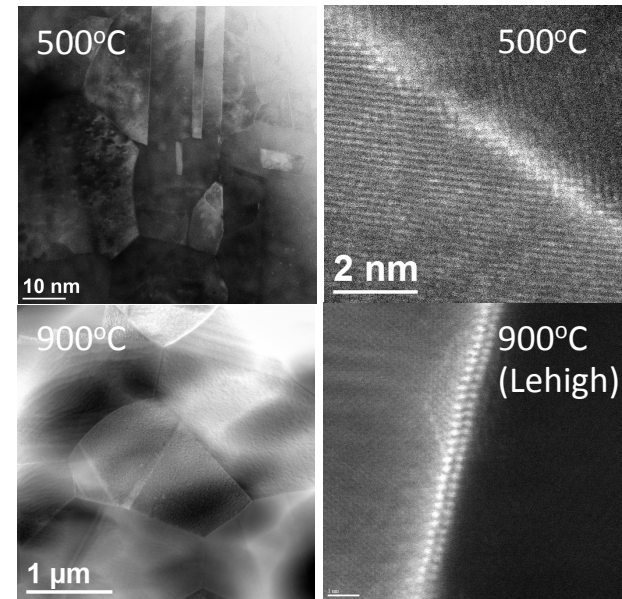
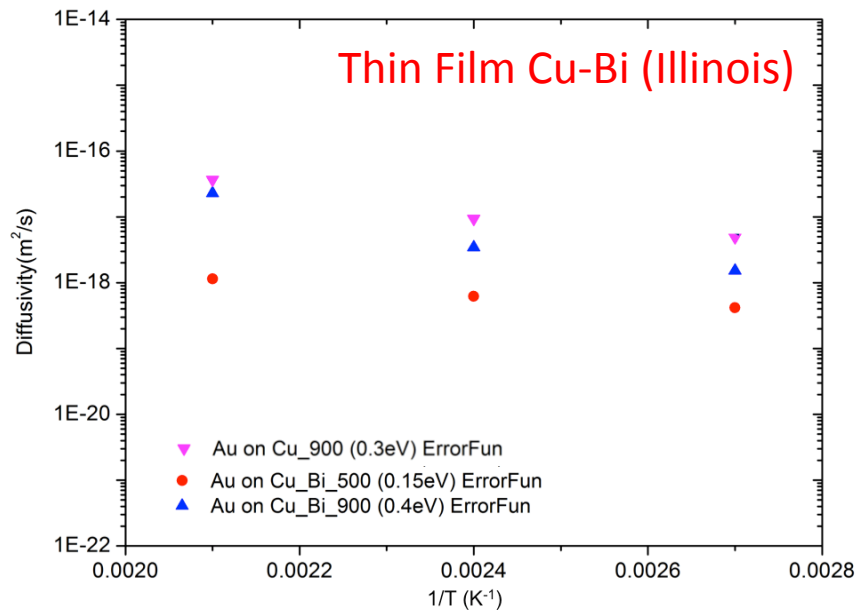
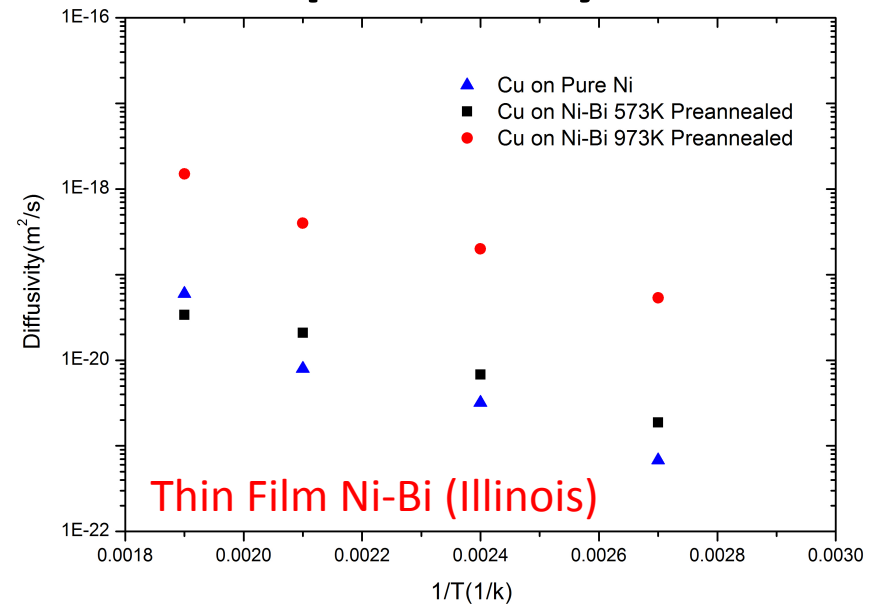
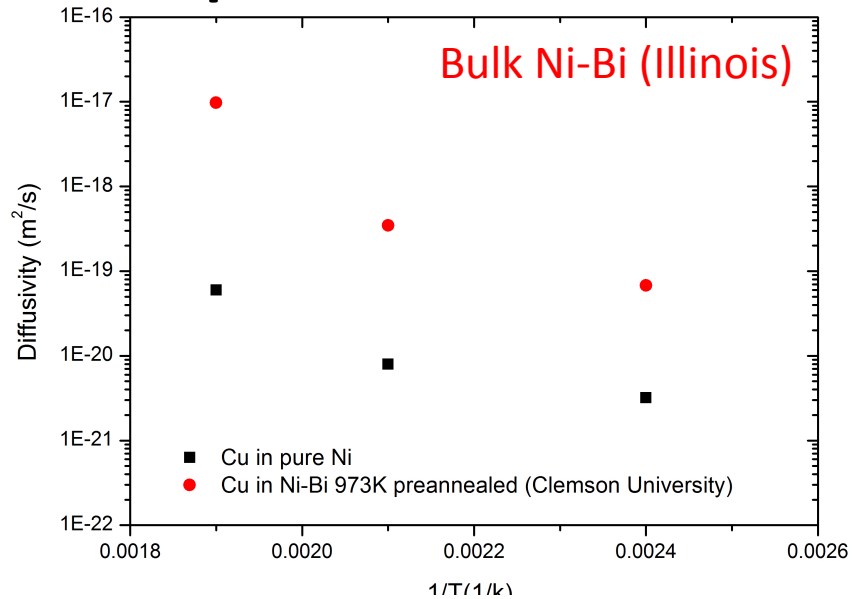
$\Delta \gamma \sim 0.3-0.5 \text{ J/m}^2$

Table I. The Mean Relative Energies of Different Grain-Boundary Complexions Occurring as Normal and Abnormal Grains in Doped and Undoped Alumina Annealed at Different Temperatures

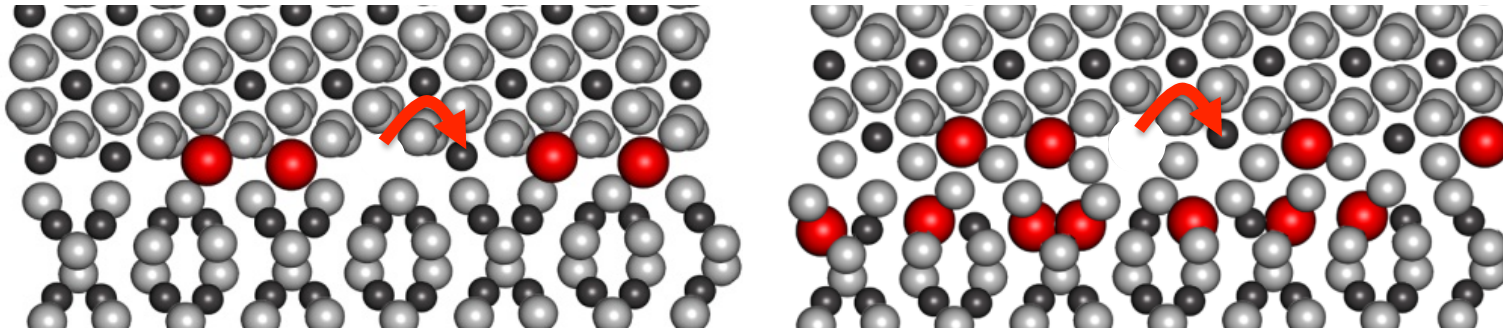
Chemistry	Temperature (°C)	Complexion	Relative energy	% energy change (complexion transition)
Undoped	1400	II (NGG)	1.11	
	2020	II (NGG)	1.08	
100 ppm-Nd <sub>2</sub> O <sub>3</sub>	1400	I (NGG)	0.95	-16
	1400	III (AGG)	0.8	
100 ppm-Y <sub>2</sub> O <sub>3</sub>	1400	I (NGG)	0.57	-46
	1400	III (AGG)	0.31	
500 ppm-MgO	1400	I (NGG)	1.07	-26
	1700	III (NGG)	0.79	
30 ppm-CaO	1200	I (NGG)	0.82	-20
	1200	III (AGG)	0.69	
200 ppm-SiO <sub>2</sub>	1200	I (NGG)	0.68	-10
	1200	III (AGG)	0.61	

Dillon et al. *JACerS* 2010

# Comparison with Other Samples/Systems



# Experimental Approach

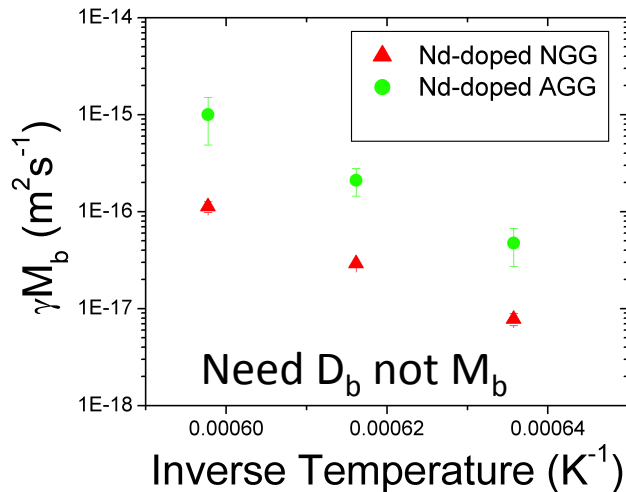


$$\Delta\gamma = \Delta\rho [RT \ln(g a_I^2 v_I^* / g \kappa_{II} a_{II}^2 v_{II}^*) - T(\Delta S_{f,I} - \Delta S_{f,II}) + (\Delta H_{f,I} - \Delta H_{f,II}) + (\Delta H_{m,I} - \Delta H_{m,II})]$$

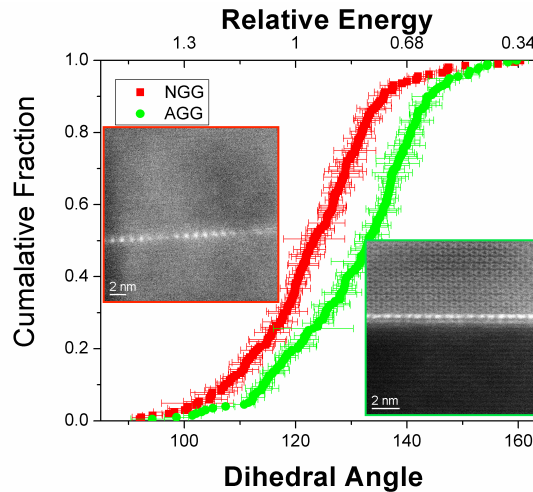
Simplifying Assumptions:  $\Delta\gamma = \Delta\rho [-T(\Delta S_I - \Delta S_{II}) + (\Delta H_I - \Delta H_{II})]$

Approach:

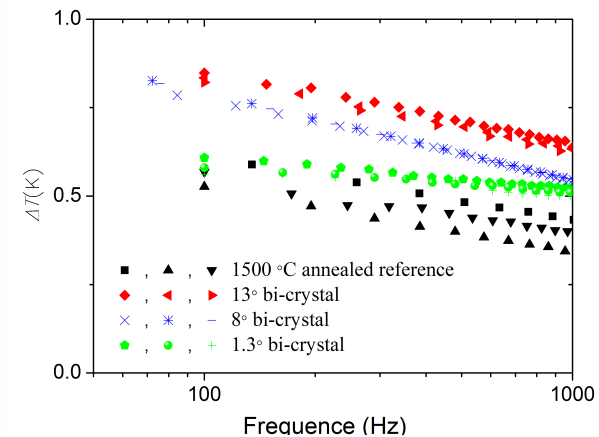
Measure Diffusivity



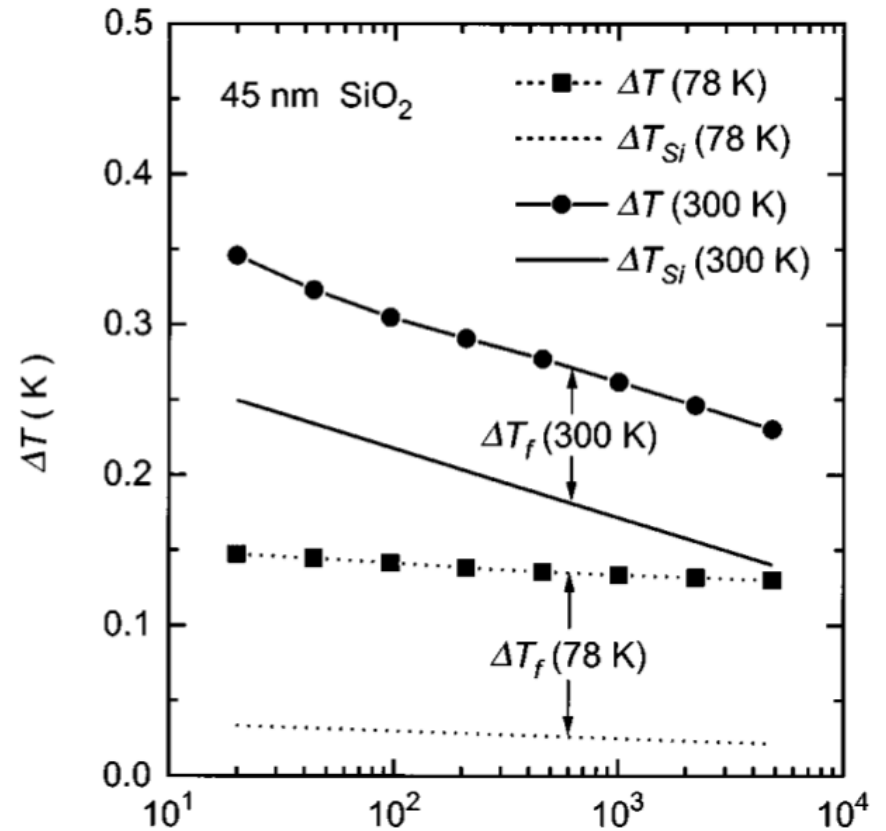
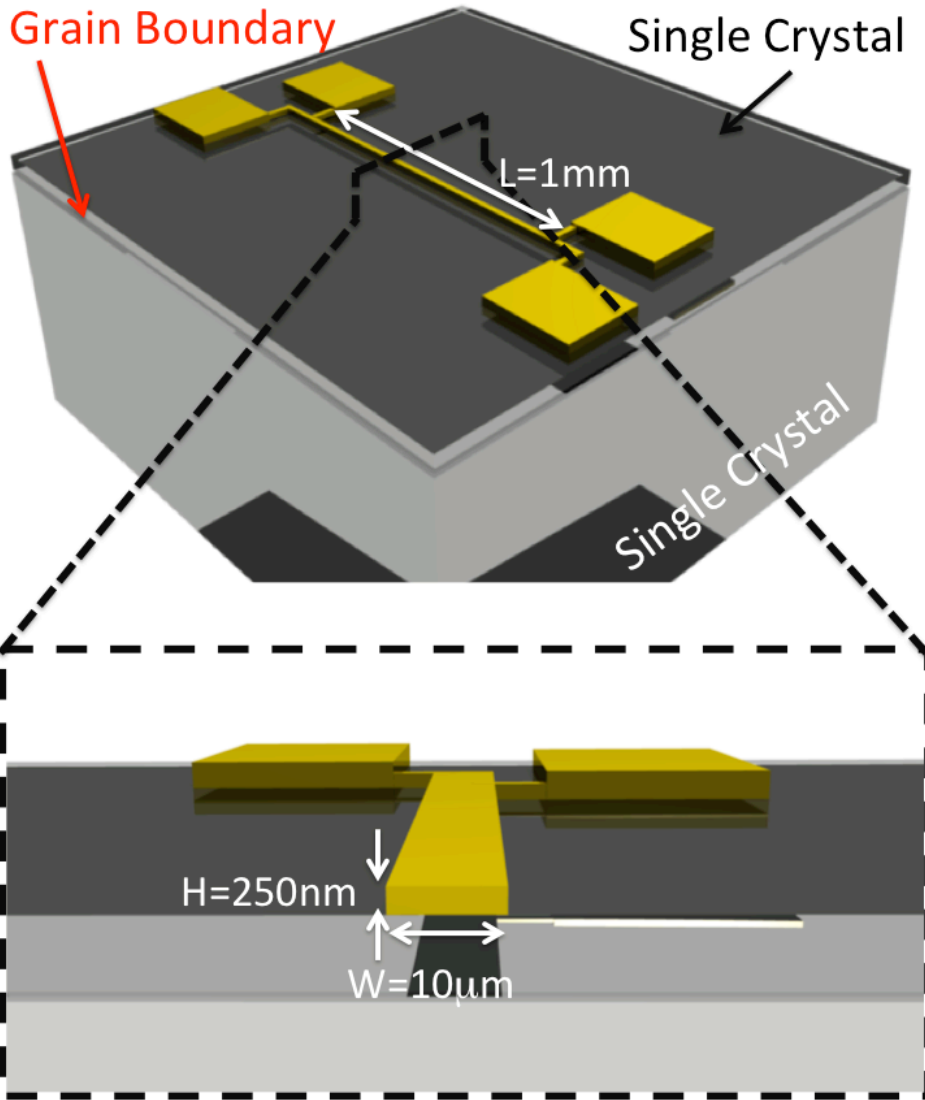
Measure Relative Energy



Measure Therm. Cond.



# Interfacial Thermal Conductance - Approach

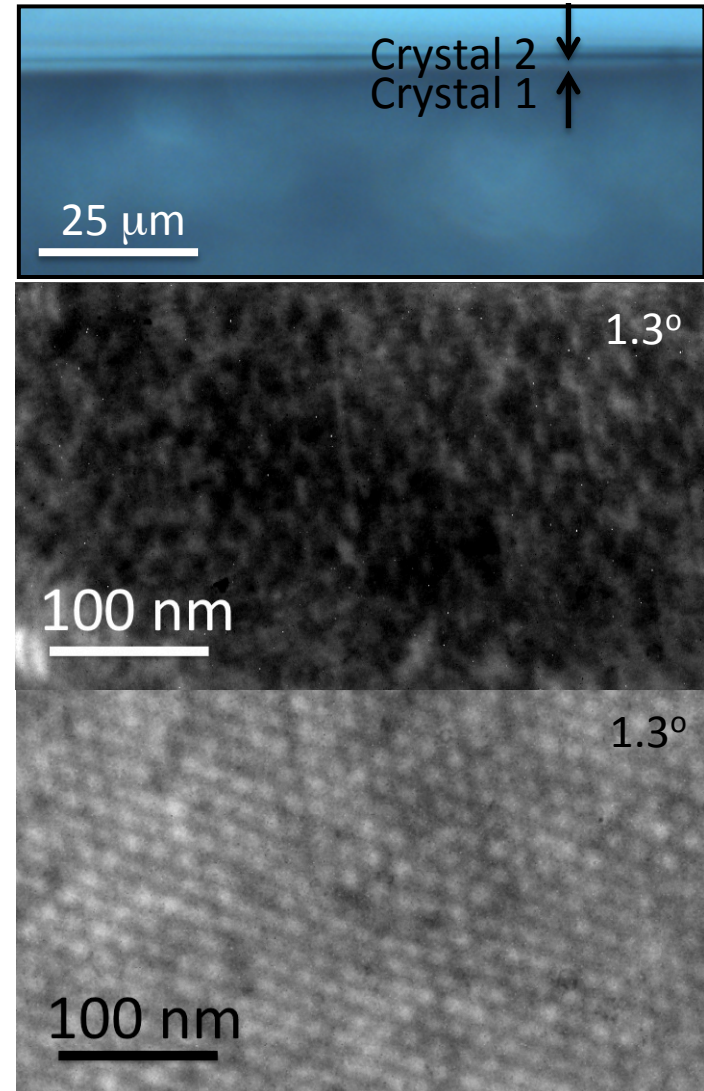
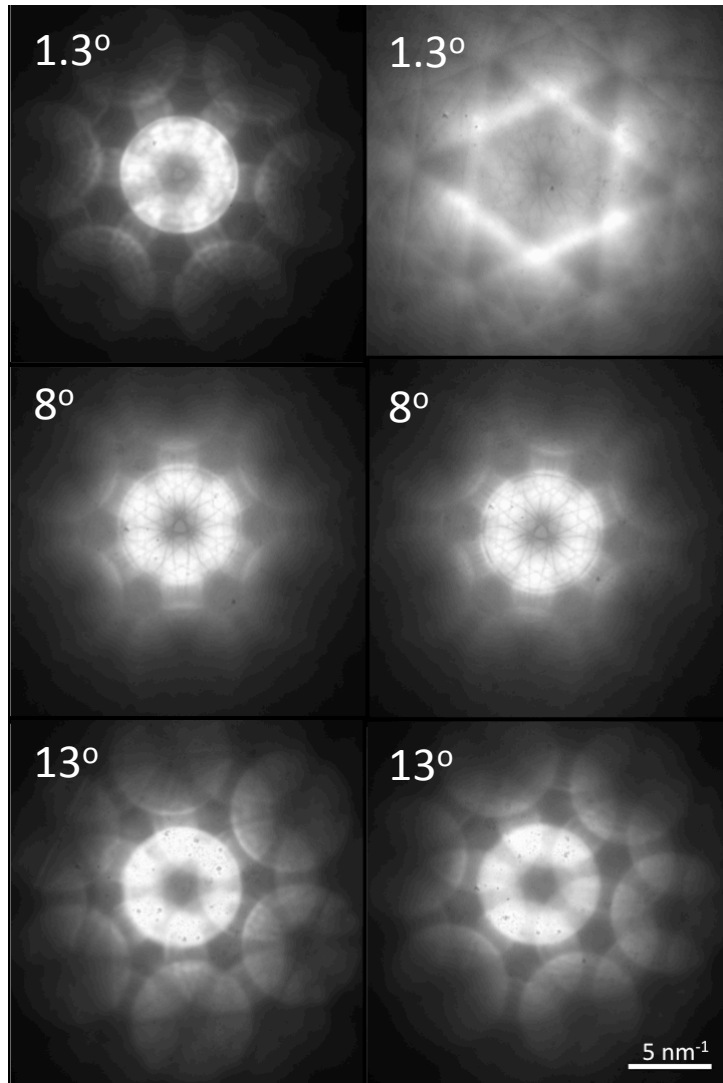


$$\Lambda = \frac{V \ln f_2 / f_1}{4\pi l R^2 (V_{3,1} - V_{3,2})} \frac{dR}{dT}$$

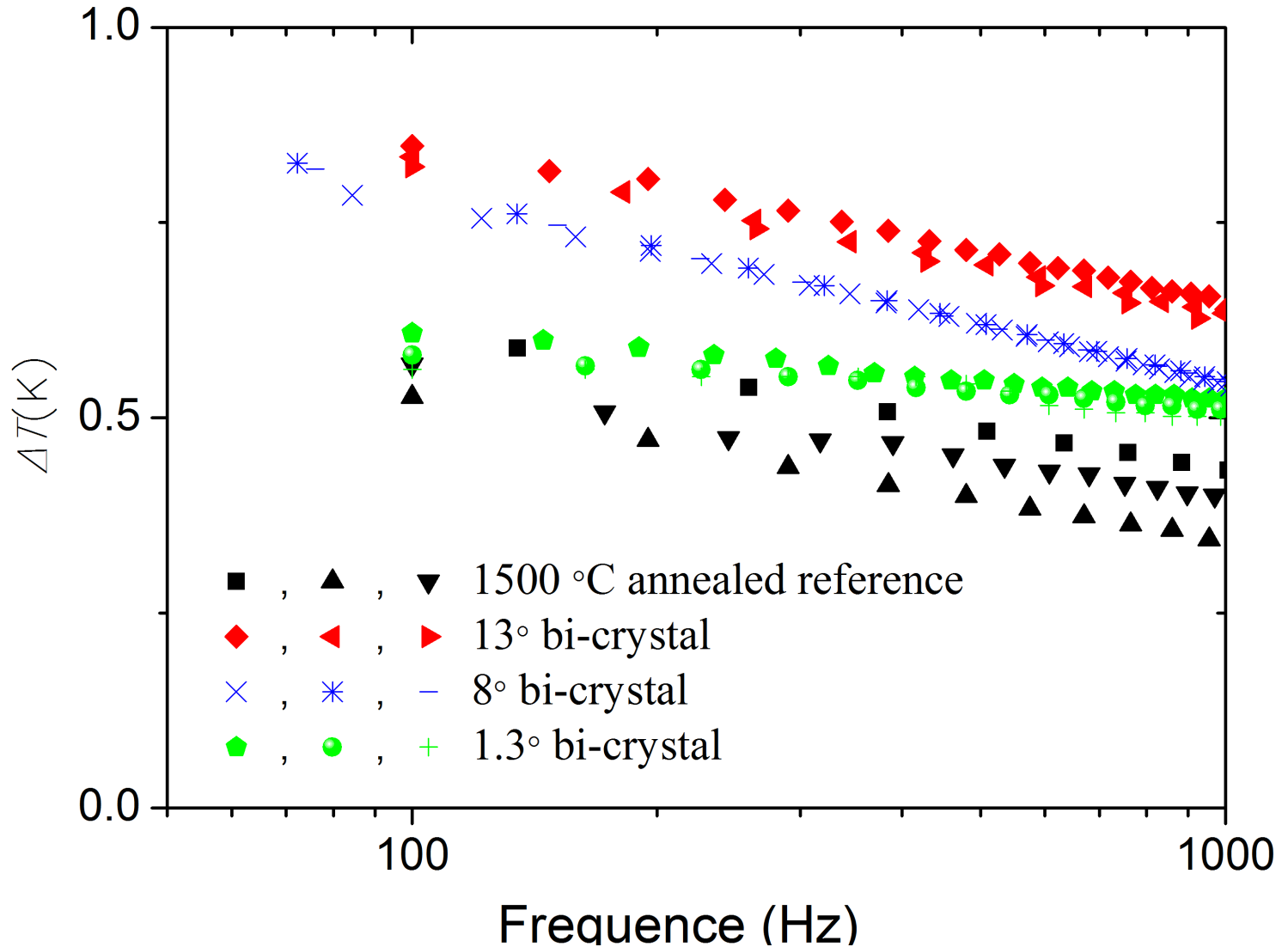
$$\Delta T_f = \frac{P}{\Lambda_a} \frac{t}{w} \quad \Lambda_a = \frac{\Lambda_i}{1 + R_I \Lambda_i / t}$$

Cahill, JAP (2002)

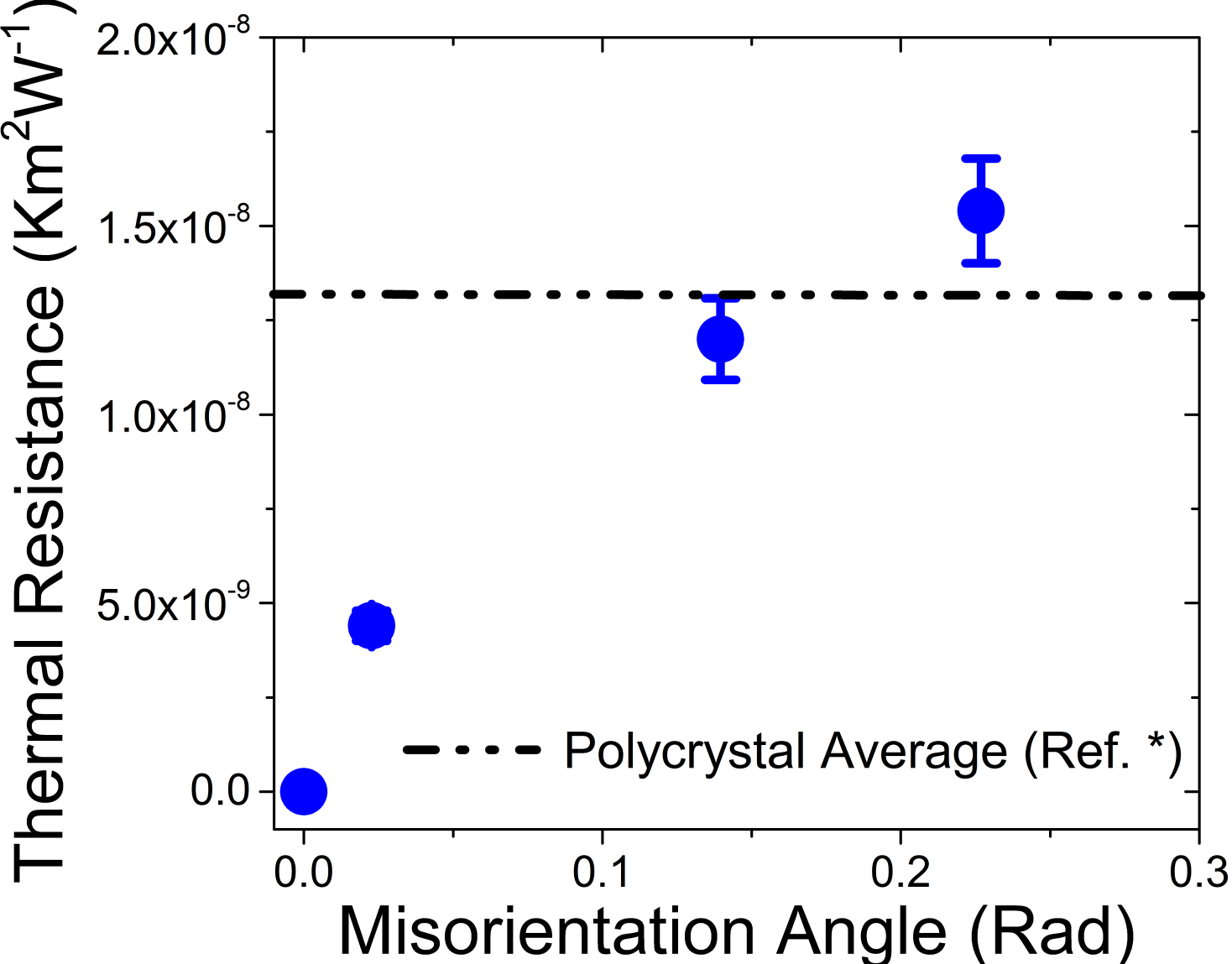
# Bicrystal Samples



# Interfacial Thermal Conductance

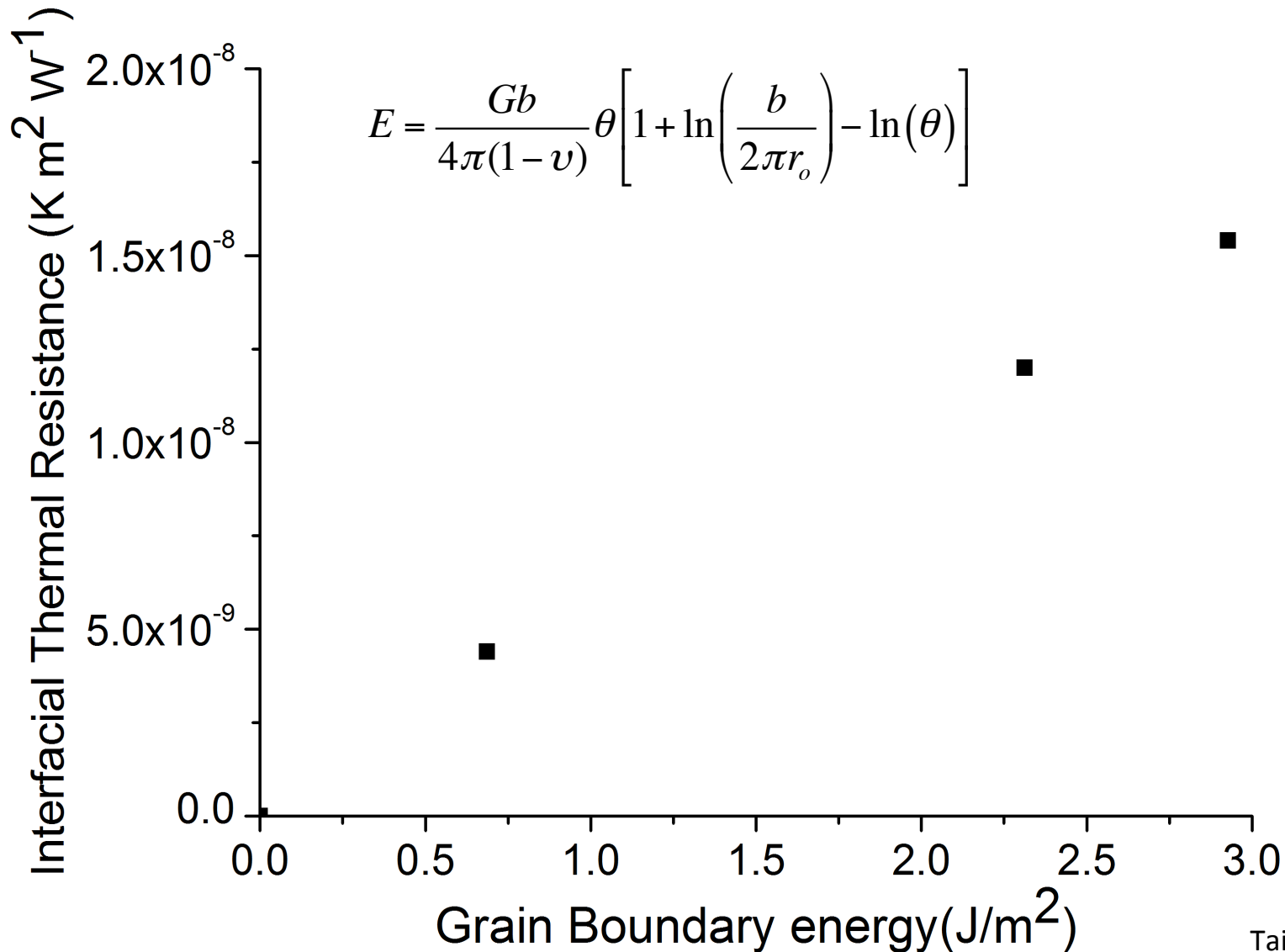


# Misorientation Effect on Kapitza Resistance



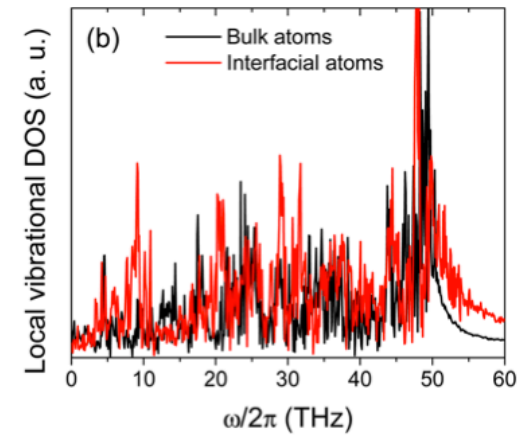
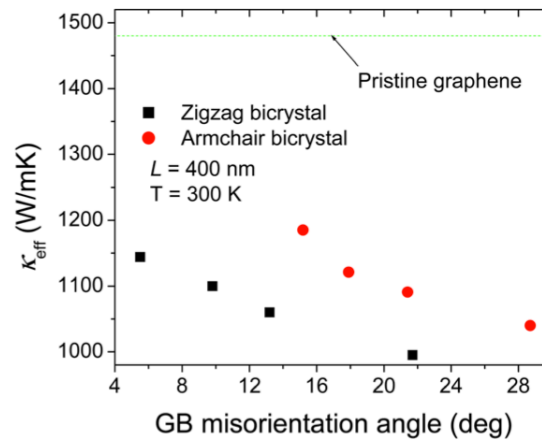
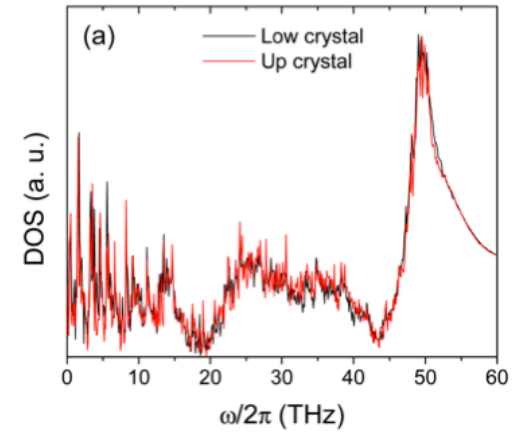
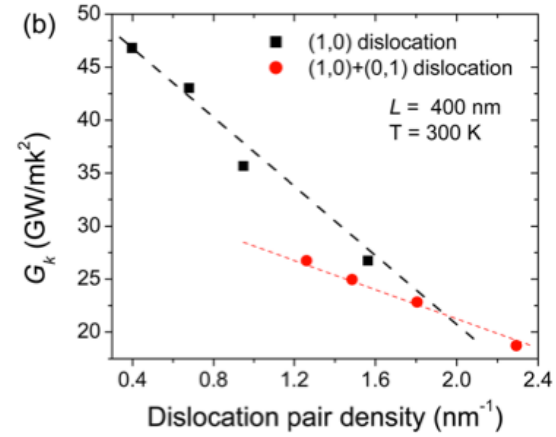
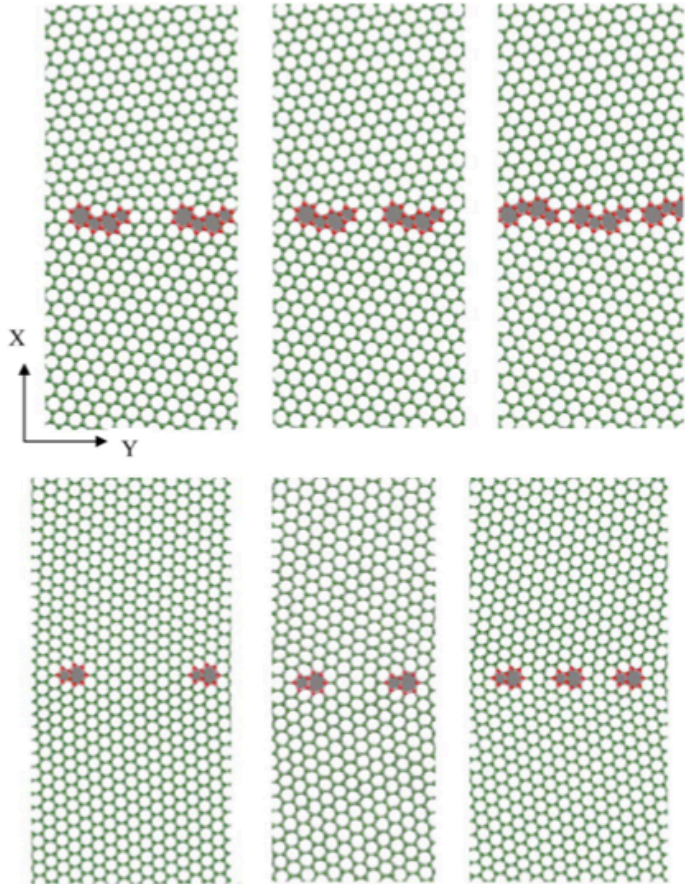
\*Smith et al. *JACerS* (2003)

# Comparison with Read-Shockley

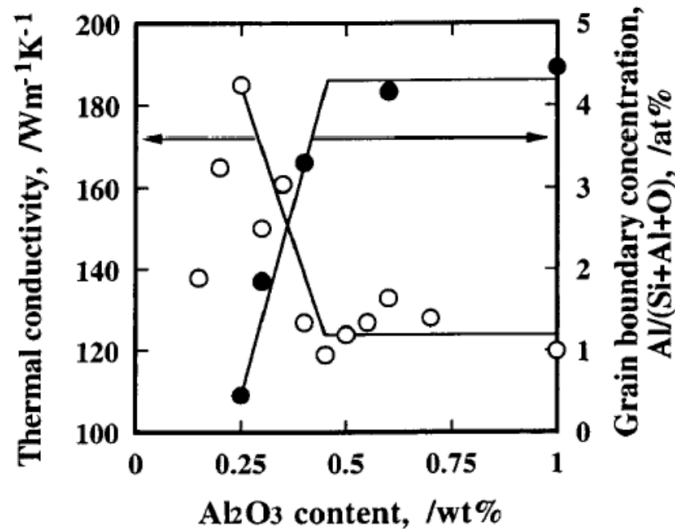
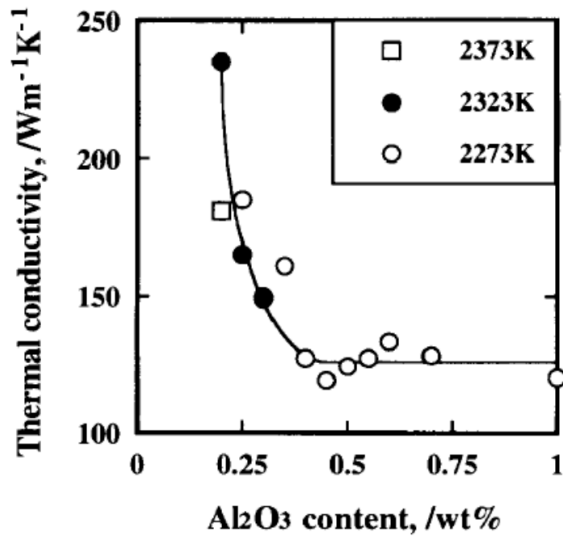




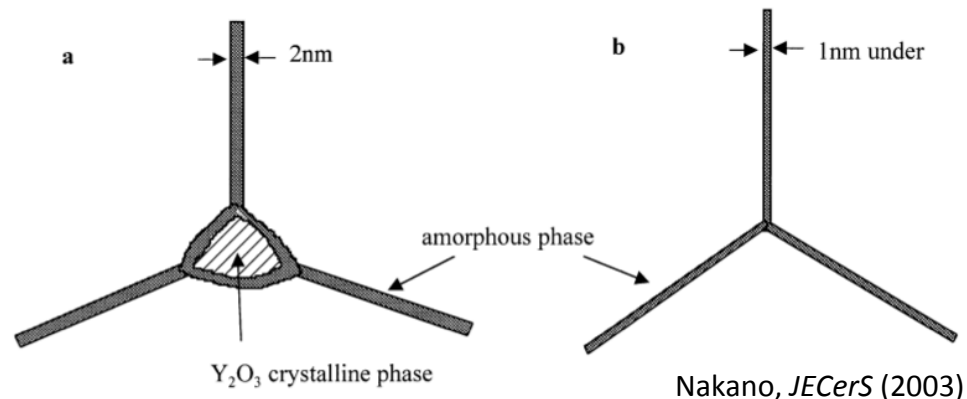
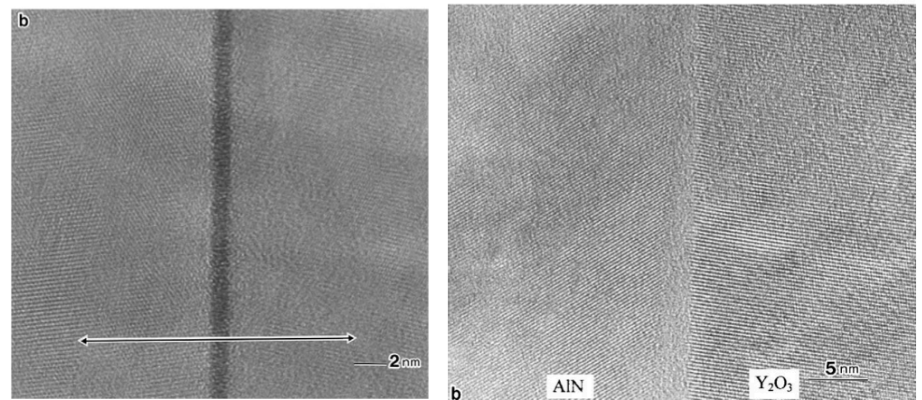
# T.C. & Grain Boundary Defects (Graphene)



# Future Work: Doped Bicystals & Complexions

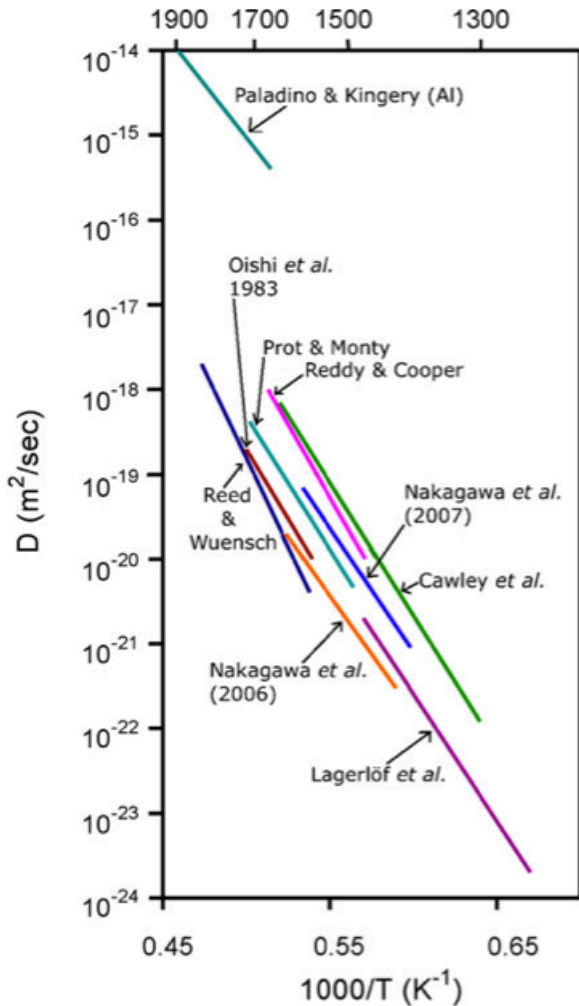


Sintering conditions	Density ( $\text{kg/m}^3$ )	Chemical composition		Grain boundary phase	Thermal conductivity ( $\text{W/m}^\circ\text{C}$ )
		Oxygen (mass%)	Yttrium (mass%)		
1900 $^\circ\text{C}$ , 20 h	3281	0.14	0.20	None	220
1900 $^\circ\text{C}$ , 100 h	3260	0.05	0.03	None	272

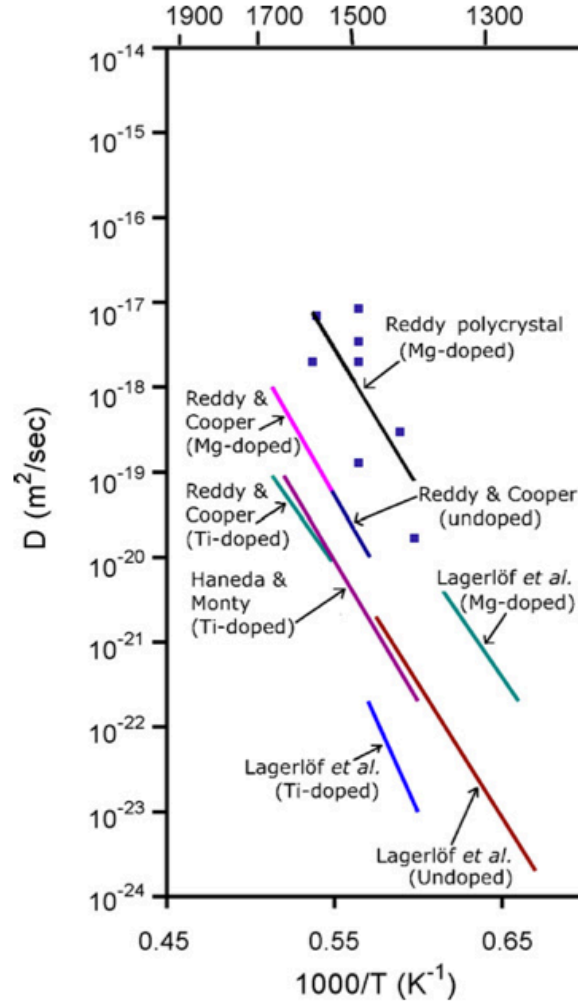


# Oxygen Diffusion in $\text{Al}_2\text{O}_3$

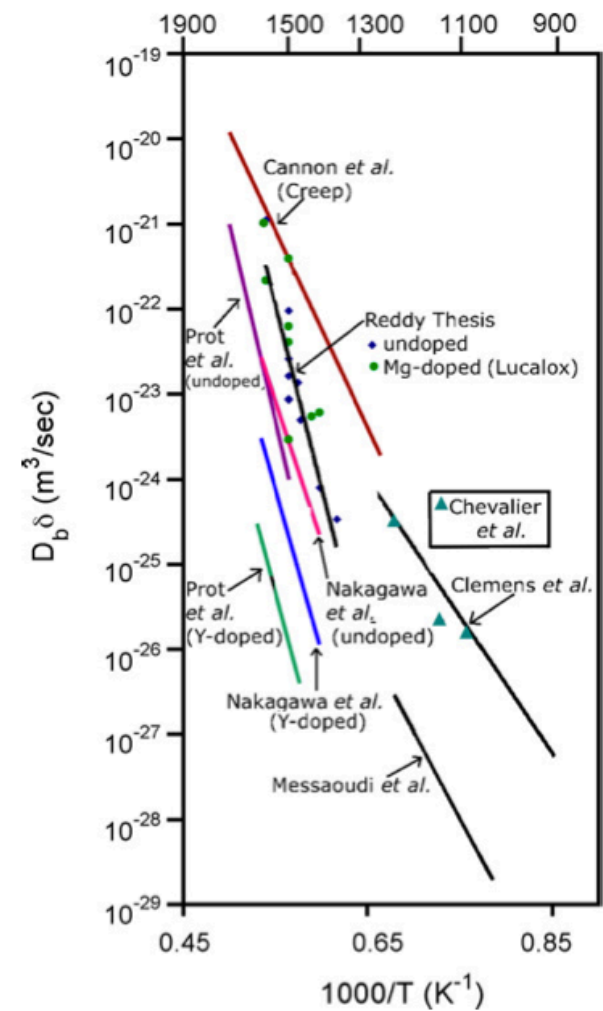
## Oxygen Lattice



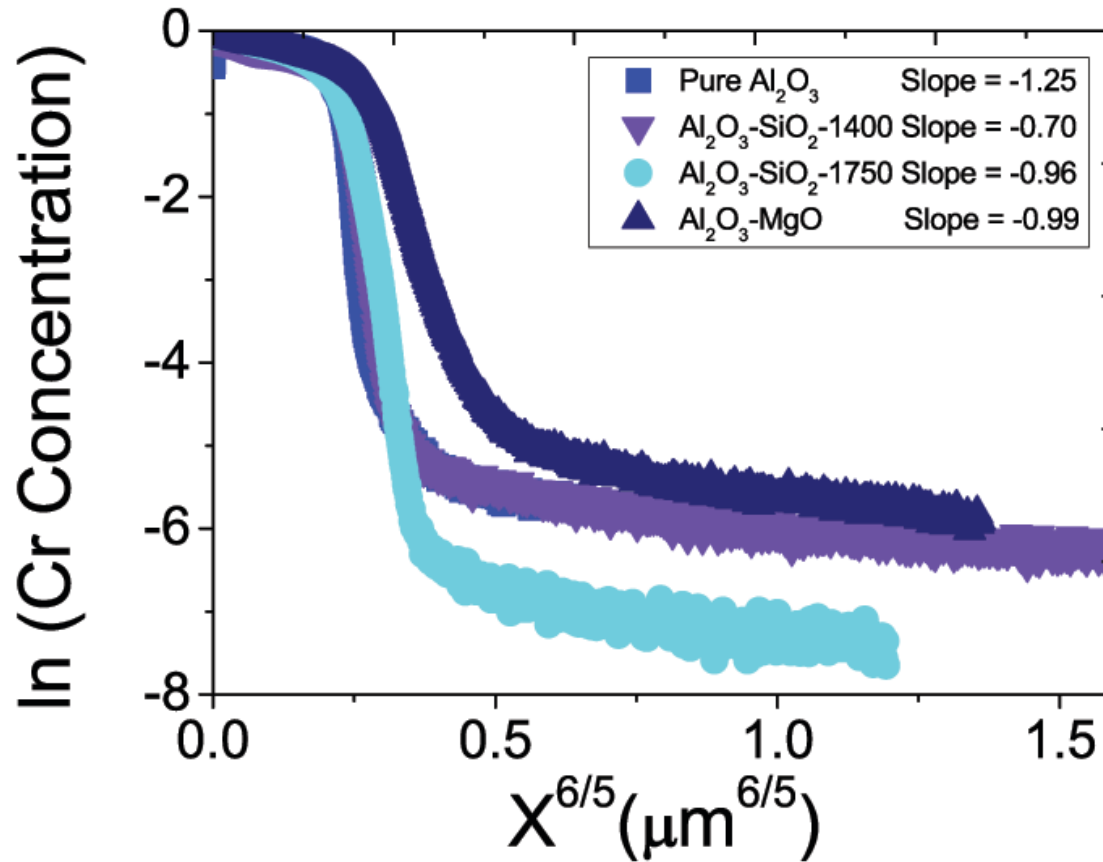
## Doped Oxygen Lattice



## Oxygen Grain Boundary



# Preliminary Tracer Diffusion

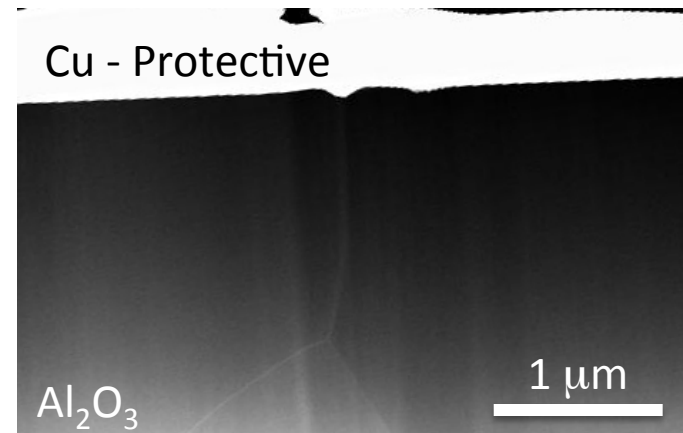
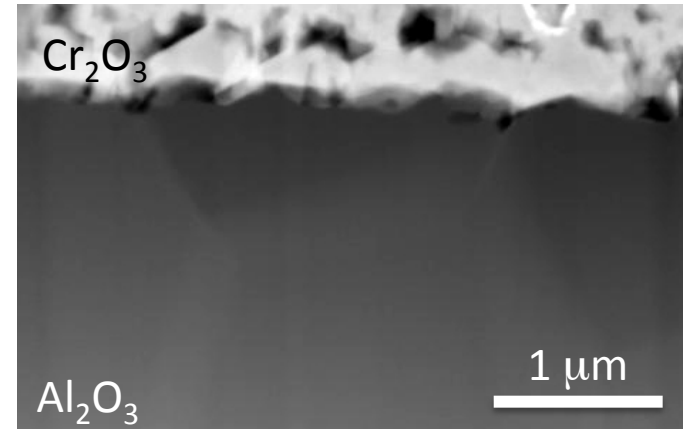
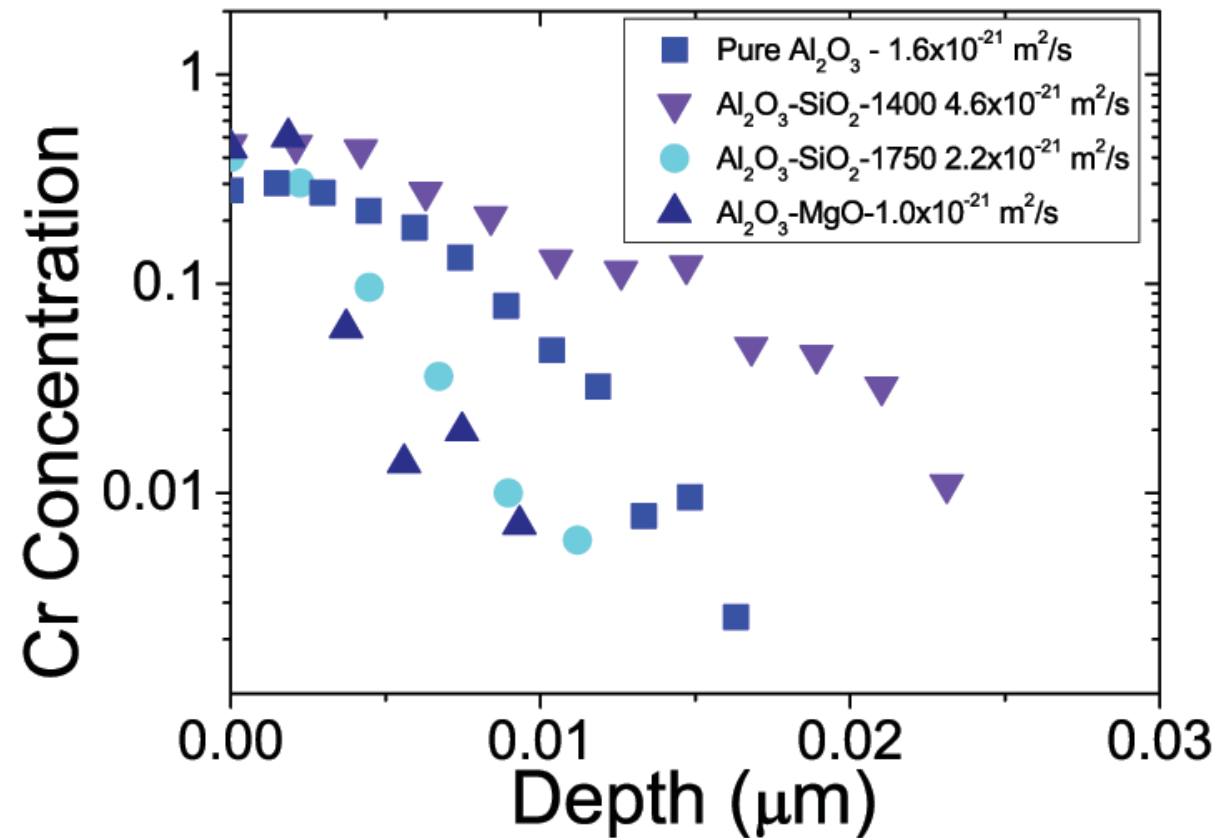


Type B



$$sD_{gb}\delta = 1.308\sqrt{\frac{D}{t}}(-\partial\bar{c}/\partial z^{6/5})^{-5/3}$$

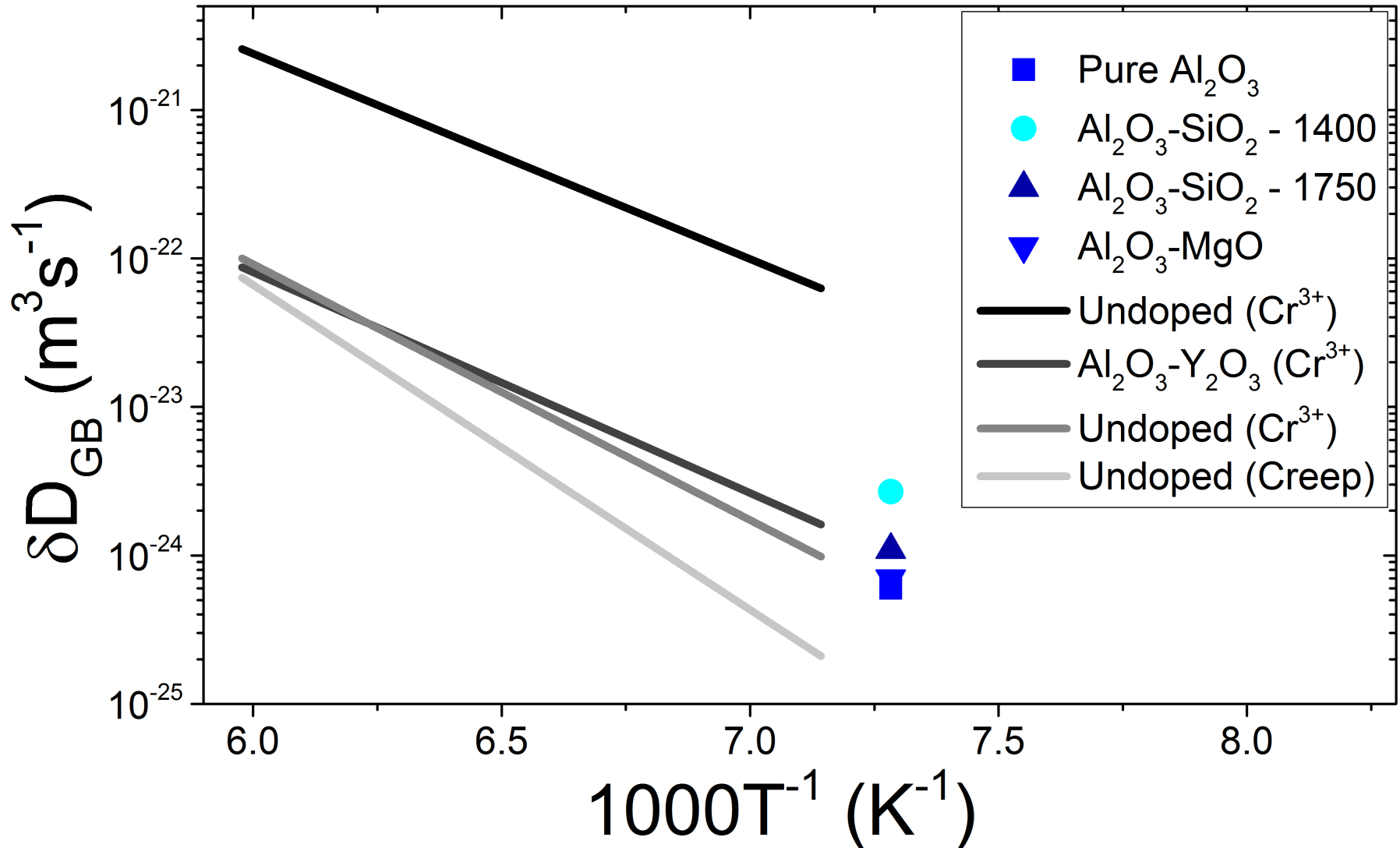
# Preliminary Lattice Diffusion



Paladino Kingery (1962)  $\Rightarrow D_{\text{Al}} = 1.7 \times 10^{-22} \text{ m}^2/\text{s}$  at  $1100^\circ\text{C}$  (Extrapolated from  $1670^\circ\text{C}$ )

Moya et al. (1995)  $\Rightarrow D_{\text{Cr}} = 1.1 \times 10^{-21} \text{ m}^2/\text{s}$  at  $1100^\circ\text{C}$

# Preliminary Al<sub>2</sub>O<sub>3</sub> Diffusivity Results



# Conclusions

- Kinetics indicate G.B. complexion transition in Ni-Bi system (similar Cu-Bi)
  - Kinetics indicate significant entropy contribution
- Kapitza resistance scales with G.B. energy for low angle boundaries
- Preliminary results suggest cation diffusion (G.B. and lattice) not strongly sensitive to complexions/dopants